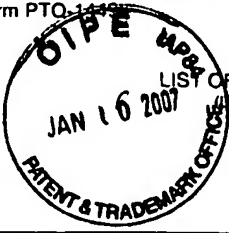


Form PTO-1449 		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2310		SERIAL NO. 10/643,680	
LIST OF ART CITED BY APPLICANT <small>(Use several sheets if necessary)</small>				APPLICANT: Kraus et al.			
FILING DATE August 18, 2003				GROUP 1762			

U.S. PATENT DOCUMENTS							
Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
BT	AA	6,203,613	03/01	Gates et al.			
BT	AB	10/196,814	07/02	Kyung-In			
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						

FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AJ							
	AK							
	AL							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
BT	AM		Park et al., "Plasma-Enhanced Atomic Layer Deposition of Tantalum Nitrides Using Hydrogen Radicals as a Reducing Agent", Electrochemical and Solid-State Letters, 4 (4) C17-C19, The Electrochemical Society, Inc. (2001).
	AN		
	AO		

EXAMINER /Brian Talbot/	DATE CONSIDERED 02/06/2007
----------------------------	-------------------------------

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

EV979437262